

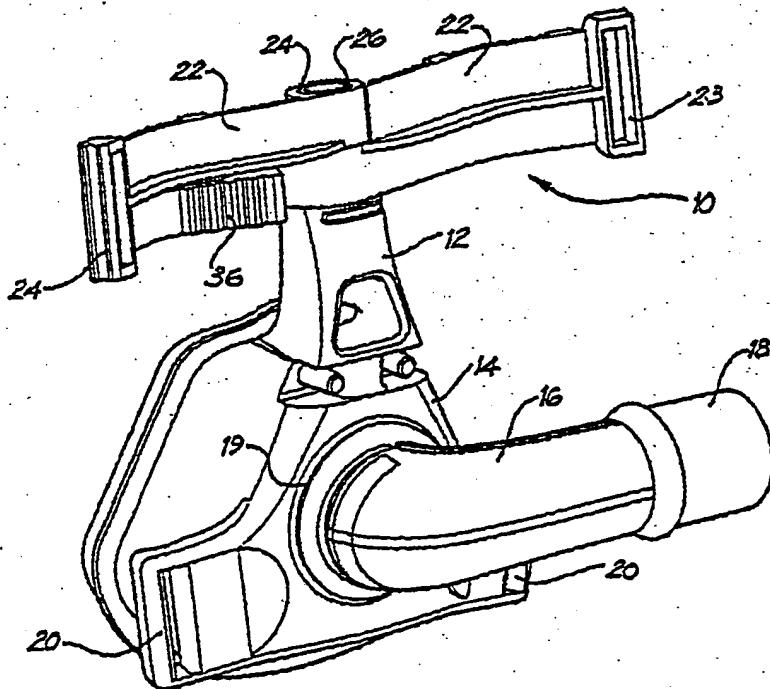
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International Bureau

INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(51) International Patent Classification 7 : A61M 16/06, A61B 9/00, 18/08	A1	(11) International Publication Number: WO 00/57942 (43) International Publication Date: 5 October 2000 (05.10.00)
<p>(21) International Application Number: PCT/AU00/00260</p> <p>(22) International Filing Date: 29 March 2000 (29.03.00)</p> <p>(30) Priority Data: PP 9499 29 March 1999 (29.03.99) AU</p> <p>(71) Applicant (<i>for all designated States except US</i>): RESMED LIMITED [AU/AU]; 97 Waterloo Road, North Ryde, NSW 2113 (AU).</p> <p>(72) Inventor; and</p> <p>(75) Inventor/Applicant (<i>for US only</i>): GUNARATNAM, Michael, Kassipillai [AU/AU]; 3 Keiley Street, Marsfield, NSW 2122 (AU).</p> <p>(74) Agent: SPRUSON & FERGUSON; G.P.O. Box 3898, Sydney, NSW 2001 (AU).</p>		<p>(81) Designated States: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG).</p> <p>Published With international search report.</p> <p>EP 1165166</p>

(54) Title: FOREHEAD SUPPORT FOR A FACIAL MASK



(57) Abstract

A forehead support (10) for a respiratory mask (14). The forehead support (10) includes a pair of arms (22). The arms (22) are each adapted to locate a forehead cushion (30). The arms (22) are also adapted to pivot relative to each other. The arms (22) are also selectively lockable at two or more angular positions relative to each other. The forehead support (10) can thus be adjusted to suit the facial topography of the wearer of the respiratory mask (14).